

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 64-076933
(43)Date of publication of application : 23.03.1989
(51)Int.Cl. C03C 3/06
C03B 8/02
C03C 4/08
C03C 4/12
(21)Application number : 62-256360 (71)Applicant : SEIKO EPSON
CORP
(22)Date of filing : 13.10.1987 (72)Inventor : KAWACHI
AKIHIKO
MIYASHITA
SATORU
ITO
YOSHITAKA
(30)Priority/ 61246006 Priority 16.10.1986
Priority number : 62 5848 date : 13.01.1987 Priority JP
62149683 16.06.1987 country : JP
JP

(54) DOPED QUARTZ GLASS AND ITS PRODUCTION

(57)Abstract:

PURPOSE: To facilitate the production of a doped quartz glass of homogeneity and a large shape, by dispersing fine particles of silica in an alkyl silicate hydrolyzate, forming sol, after its pH is adjusted, then drying and heating the sol.

CONSTITUTION: Alkyl silicate is hydrolyzed using an acidic catalyst, fine particles of silica are dispersed in the hydrolyzate, and the silica dispersion is adjusted in its pH to 3W6. Then, dopants containing at least one elements or dopant solutions are added to the silica dispersion to form a sol. The sol is converted into the gel, the gel is dried, and the dry gel is heated into a glass. The dopants are selected according to the purposes for the doped quartz glass, and the process according to the present invention can use any element substances as a dope.

LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]